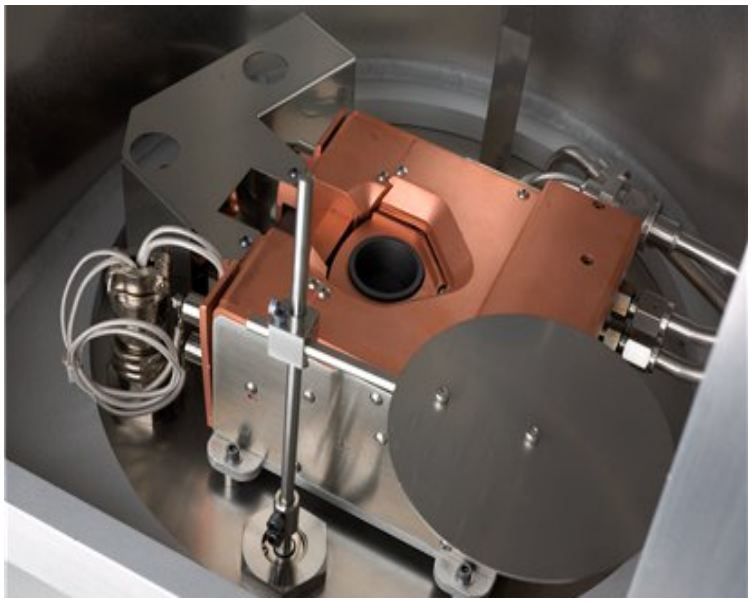
Nexdep Electron Beam and Thermal Evaporator



A filament emits a magnetically focused high energy beam of electrons which is swept within a crucible of deposition material. On the surface substrate with lithographical pattern or bare substrate, deposits thin film of metal such as Ni. Cr, Al, Au, Pt, Mo, and several layer film structure such as Ti/Al/Ni/Au.

Specifications

- Base pressure of <5 x 1^{-7} Torr
- 16 W x 16 D x 20 “ H aluminum high vacuum chamber
- Automated system control
- Programmable 2-axis sweep controller
- Thermal deposition system of 2500 V transformer
- Six of electron beam source pockets
- 2 of thermal sources
- Control outputs for 4 sources simultaneously
- Backside Quartz IR substrate Heating
- Source to substrate distance of 358 mm for Thermal and 399 mm for e-beam